Radiation Induced Br-Transfer from Ethylbromide to Triethylsilane

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The radiolysis of deoxygenated triethylsilane (Et₃SiH) was studied in the presence of various concentrations of ethylbromide (EtBr) as a function of the radiation dose. Chain reactions are leading to rather high yields of Br-containing final products, *e.g.* using 0.93 mol/dm³ EtBr we obtained: $G_i(Et_3SiBr) = 138$, $G_i(HBr) = 40$, $G_i(Br_2) = 15$ and $G_i(Et_3Si-SiEt_3) = 6$, in addition to small amounts of unidentified oligomers. Based on the knowledge from previous steady-state and pulse radiolysis studies of Et_3SiH , a probable reaction mechanism is postulated to allow explanation of the present results.

Introduction

The chemistry of silanes, especially of organopolysilanes, where the backbone is a linear chain of silicon atoms, has recently attracted much interest. In order to better understand the reaction mechanism, halogenated silanes were used. In an earlier work by Ihlein et al. [1] several halogenated silanes in 2-methyltetrahydrofuran have been used for studies on the readiation induced formation of specific radicals at -196 °C under steady-state conditions. The observed absorption spectra were attributed to the corresponding radical anions and neutral species. The reactivity towards the free electrons (e_{aq}) is found to decrease with increasing number of methyl groups and to rise with growth of phenyl groups of the silanes. Lugovoi et al. [2] studied the radiation induced oxidation of ethyldichlorosilane, which results in the formation of chlorine-containing disiloxane. In addition to this a radical-chain process has been observed in the co-telomerization of ethylene and 1-hexene with ethyldichlorosilane [3, 4]. Pure triethylsilane (Et₃SiH) has been a subject of rather extensive steady-state and pulse radiolysis investigations [5]. As a consequence of the radiolysis, 19 final products in deoxygenated as well as in N2O saturated Et₃SiH have been found and their initial G-values

Finally, the observation of polysilane radical anions [6] and the effect of side chains studies by pulse radiolysis have been reported recently [7].

The aim of the present studies was to investigate the possibility of radiation induced transfer of a halogen atom from a halogenated organic compound, *e.g.* ethylbromide (EtBr), to triethylsilane (Et₃SiH) in airfree media.

Experimental

The chemicals used were of p. A. purity (Merck, Darmstadt). Triethylsilane was further purified as previously described [5]. Prior to irradiation high purity argon was bubbled through the solutions in the irradiation vessels for about 1 h in order to remove oxygen. Solutions of various concentrations of EtBr in Et₃SiH were irradiated as a function of radiation dose.

A "Gammacell 220" (Atomic Energy of Canada Ltd.) was used as 60 Co- γ -source. The dosimetry was performed by means of ferrous-copper dosimeter [8] under the same experimental conditions (dose rate: 41 Gy/min)⁺⁺.

The analysis of the Et₃SiH/EtBr system irradiated at various doses was performed by GC ("Carlo Erba

 $⁽G_i)^+$ determined. The total transient absorption with $\lambda_{max}=260$ nm disappears with an apparent rate constant of $k=1.85\cdot 10^9~M^{-1}s^{-1}$.

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⁺ G_i = initial G-value represents the yield (number of molecules produced per 100 eV absorbed energy) of final products calculated from the tangent through the coordinate origin to the yield-dose curve.

 $^{^{++}}$ 1 Gy = 100 rad = 6.24 · 10¹⁵ eV/g sample.

Fractovap 2300"; porapax Q Se 30 10% CPS 80/100; temperature upto 250 °C). The product yields were determined by comparison with the concentration of standard samples. Some analyses were carried out by combined GC/MS (Varian-Aerograph and Varian MAT CH7A with data system)⁺⁺⁺.

Results

Various concentrations of EtBr (0.23, 0.50, 0.93, 1.30, 1.75 and 2.69 mol/dm³) in Et₃SiH were used. As a consequence of the radiolysis of the Et₃SiH/EtBr-system two Br-containing products (HBr and Et₃SiBr) in addition to hexaethyldisilane (Et₃Si-SiEt₃), Br₂ and a mixture of unidentified oligomers were obtained. Fig. 1 illustrates the course of the EtBr decomposition ($G_i = 58$) and the formation of Et₃SiBr ($G_i = 32.8$) and HBr ($G_i = 19.3$) as a function of dose.

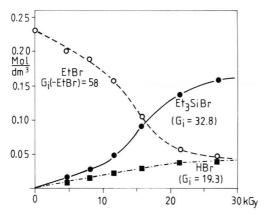


Fig. 1. Radiolysis of 0.23 mol/dm³ ethylbromide (EtBr) in deoxygenated triethylsilane (Et₃SiH) with formation of Et₃SiBr and HBr as a function of dose.

It is to be noted that the yield of Et_3SiBr is nearly a mirror-image of the EtBr decrease. The rather high product yields indicate the occurrence of chain reactions. The shape of the curves, however, strongly changes with increasing EtBr concentration. Using 0.93 mol/dm³ EtBr, the yield of Et_3SiBr is strongly increased ($G_i = 138$) and is proportional to the absorbed radiation dose. Also the yields of HBr ($G_i = 40$) and the decomposition of EtBr ($G_i = 205$) are increased (Fig. 2).

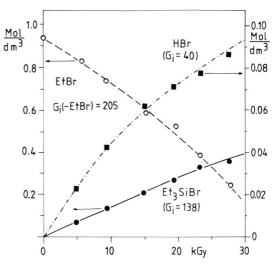


Fig. 2. Decomposition of EtBr as well as formation of Et_3SiBr and HBr from 0.93 mol/dm^3 EtBr in air-free Et_3SiH as a function of dose.

A further increase of the EtBr content in the deoxygenated Et_3SiH resulted in a decrease of the product yields as shown in Fig. 3. The radiation induced decomposition of EtBr is also reduced. Under these conditions a recombination of the radicals very likely takes place leading to reformation of the starting compounds. This effect became even more pronounced with further increase of the EtBr-concentration up to 2.68 mol/dm^3 , where $G_i(HBr) = 10$ and $G_i(Et_3SiBr) = 30$.

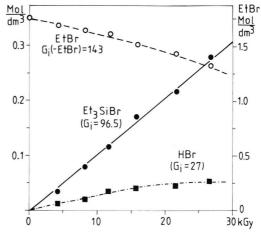


Fig. 3. Product formation (Et₃SiBr and HBr) and EtBr consumption by radiolysis of 1.75 mol/dm³ EtBr in air-free Et₃SiH as a function of dose.

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For a better survey the G_i-values obtained from all experimental series are compiled in Table I. Obviously the highest G_i-values of the products are observed by using 1.3 mol/dm3 EtBr in Et3SiH.

Table I. Initial G-values (Gi) of EtBr consumption and products formed by radiolysis of Et₃SiH in the presence of various EtBr concentrations.

EtBr G_i -values (mol/dm^3)					
in	Consumpt.				
Et ₃ SiH	of EtBr	Et ₃ SiBr	HBr	Br_2	$Et_3Si-SiEt_3$
0.23	58	32.8	19.3	5	n.d.
0.50	90	50	20	8	8
0.93	205	138	40	15	6
1.30	250	140	44	n.d.	n.d.
1.75	143	96.5	27	25	n.d.
2.68	85	34	12	20	5

Discussion

The primary radiolysis products resulting from Et₃SiH and their G_i-values (given in brackets) are presented by the brutto reaction (1) [5]:

$$Et_{3}SiH \longrightarrow H, e_{s}^{-}, (Et_{3}SiH^{+}.e^{-}), H_{2},$$

$$(3.60)$$

$$\dot{C}H_{3}, \quad \dot{C}_{2}H_{5}, \quad Et_{3}\dot{S}i,$$

$$(0.075) \quad (3.60) \quad (3.75)$$

$$Et_{2}\dot{S}iH, \quad CH_{3}\dot{C}HSi(H)Et_{2},$$

$$(3.60) \quad (0.27)$$

$$\dot{C}H_{2}CH_{2}Si(H)Et_{2}, \quad \dot{C}H_{2}Si(H)Et_{2}$$

$$(0.17) \quad (0.075)$$

$$(1)$$

The most important species in the present case are: e_s^- , (Et₃SiH⁺.e⁻), H, Et₃Si, Et, Et₂SiH. At lower EtBr concentrations in Et₃SiH the following reaction steps are very likely:

$$\begin{array}{lll} EtBr + e_s^- \to Et^{'} + Br^- & (2) \\ EtBr + (Et_3SiH^+, e^-) \to Et^{'} + Br^- + Et_3SiH^+ & (3) \\ Et_3SiH^+ + Et_3SiH \to Et_3SiH_2^+ + Et_3Si & (4) \\ Et_3SiH_2^+ + Br^- \to Et_3Si + H_2 + Br & (5) \\ Et_3SiH + Br \to Et_3Si + HBr & (6) \\ EtBr + H \to Et^+ + HBr & (7a) \\ \to C_2H_6 + Br & (7b) \\ EtBr + Et_3Si \to Et^+ + Et_3SiBr & (8a) \\ \to Br + Et_4Si & (less probable) & (8b) \\ EtBr + Et_2SiH \to Et_2SiH + Br & (9a) \\ \to Et_3SiH + Et_2SiH \to Et_2SiH_2 + Et_3Si & (10) \\ \end{array}$$

According to reactions (2), (3), (7a), (8a) and (9b) Et radicals are formed, which can initiate a chain reaction, namely:

$$Et_3SiH + Et \rightarrow Et_3\dot{S}i + C_2H_6$$
 (11)

The EtaSi radicals thus produced, together with those formed by reactions (4) to (6) and (10) are consumed by reaction (8a) resulting in the main product, Et₃SiBr and again Et' radicals. A second chain process is started by the formation of Br species (see reactions (5) and (9a)). The Br transients are consumed by reaction (6), whereby HBr and Et₃Si transients are resulting. Reaction (7a) also contributes to the formation of HBr. Probably to a small extent the radical cations Et₃SiH⁺ can react with Br⁻ by an electron transfer in competition to reaction (4).

$$Et_3SiH^+ + Br^- \rightarrow \dot{B}r + Et_3SiH^* \rightarrow Et_3\dot{S}i + H$$
 (12)

In this case three reactive species can be formed (Br, H and Et3Si), which are consumed as shown above.

With increasing EtBr concentration a direct radiolysis starts to play a role, namely:

$$EtBr \longrightarrow EtBr^* \longrightarrow Et' + Br'$$

$$Et^+ + Br^-$$
(13a)
(13b)

Et' and Br' transients are strongly contributing to an increase of the main product yields. The Et+ transients can be scavenged in the bulk of the solution, e.g.:

$$Et^{+} + Et_{3}SiH \xrightarrow{\hspace{1cm}} EtH^{+} + Et_{3}Si \qquad \qquad (14a)$$

$$Et^{+} + Et_{3}SiH^{+} \qquad \qquad (14b)$$

$$\rightarrow$$
 Et' + Et₃SiH⁺ (14b)

$$EtH^{+} + e_{s}^{-} \rightarrow EtH^{*} \rightarrow Et^{-} + H$$
 (15)

The possible fate of Br is shown by reactions (5) and (12). Clearly, these processes explain the strong rise of the product yields presented in Fig. 2 compared to those in Fig. 1.

With further increase of the EtBr concentration, however, a decrease of the product yields is observed (Fig. 3 and Table I). This effect can be referred to back reactions initiated by the higher yield of the species resulting from reactions (13) to (15), which can lead to a reformation of the starting compounds, e.g.:

$$Et' + Br' \rightarrow HBr \tag{16}$$

$$Et_3\dot{S}i + H \rightarrow EtSiH$$
 (17)

Finally, it might be mentioned, that besides the formation of various products [5] the Et₃Si radicals can also combine to give hexaethyldisilane as shown in Table I (see reaction (18)). By increasing the concentration of EtBr in Et₃SiH, the probability of Br atom combination to Br_2 is rised (Table II, reaction (19)).

$$2 Et_3Si \rightarrow Et_3Si - SiEt_3$$
 (18)

$$2 Br \rightarrow Br_2 \tag{19}$$

Conclusion

The radiation induced formation of Et₃SiBr and HBr from Et₃SiH using various concentrations of EtBr in absence of air was investigated as a function of radiation dose. The highest product yields, $G_i(Et_3SiBr) = 140$ and $G_i(HBr) = 44$, were achieved by using 1.30 mol/dm³ EtBr. Taking into considera-

tion the knowledge obtained by previous steady-state and pulse radiolysis studies of Et₃SiH [5], a probable reaction mechanism involving chain reaction steps is presented. The method can be used for production of Et₃SiBr.

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